

LIQUID SOURCE VAPORIZATION SYSTEM

ABSTRACT

Provided is a liquid source vaporization system applied to a semiconductor process apparatus, including: a vaporization device (20), a liquid source pipeline (10), a purging pipeline (40), a first control unit (50), an output pipeline (30), a tail gas treatment pipeline (62), and a second control unit (70). The first control unit (50) is configured to selectively control the purging pipeline (40) or the liquid source pipeline (10) to be communicated with the vaporization device (20); and the second control unit (70) is configured to selectively control the tail gas treatment pipeline (62) or the output pipeline (30) to be communicated with the vaporization device (20). The system can solve the problem of a residual liquid process medium in a pipeline after each use in the related art.

FIGURE 1